

Abstract

The present invention relates to a method for calibrating a metrology stage in at least two dimensions using an artefact plate having marks forming a pattern, comprising the steps of:

5 placing the artefact plate on the metrology stage in at least three positions, assuming the geometrical properties of the metrology stage and the artefact plate, and the positions of the artefact plate for each measurement, forming a model predicting the measurements of the artefact plate, measuring

10 the marks by the metrology stage, and inverting said model to improve the assumptions on metrology stage and artefact plate.